

**THE FORUM ON THE SCIENCE AND TECHNOLOGY OF
SILICON MATERIALS 2001
Shonan Village Center**

Organized by: The Organizing Committee of Silicon Materials Science and Technology Forum
Supported by: The 145th Committee on Processing and Characterization of Crystals of JSPS
The Japan Society of Applied Physics

Organizing Committee

Chairman: K. Sumino (Professor Emeritus, Tohoku University)

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H. Yamada-Kaneta (Fujitsu Laboratories Ltd.): Program Chair	
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T. Kitano (NEC Corporation)	Y. Udo (Toshiba Corporation)

Assistants: H. Takahashi, K. Tanahashi (Fujitsu Laboratories Ltd.)

Conference Site: Shonan Village Center, International Conference Hall (See, separate sheet)

Dates : Start at 13:00 Nov. 26 (Monday), End at 15:30 Nov. 28 (Wednesday), 2001

Forum aims to:

1. Activate beyond-border confluence of basic and application researches that are indispensable for establishing the technology of device-oriented high-quality silicon materials.
2. Develop all-attendee-participating discussion that bears the breaking-through of the facing problems in the device fabrication technologies and industries
3. Re-educate researchers and engineers who are concerned with the scientific and/or technological fields.

Scope: To develop and innovate the technologies and their research basis of the device-oriented high-quality silicon materials, we hold this Forum that has the above-mentioned purposes. Though the Forum mainly comprises 29 invited talks, poster presentations are also available. Poster papers are printed in the Forum Proceedings together with those of invited papers. Those who wish to present poster papers are requested to prepare the manuscripts of papers and send them to us as described below. There are ample times for poster presentations with a preceding 4 minute talk for each paper.

Manuscripts of papers for poster presentation:

Manuscript should be prepared in the camera ready form with A4-size high quality white sheets. There is no special format or limit for the number of pages. Two copies of the manuscript should be sent to the registration office given below by **October 10, 2001**.

Fees:	Type-A: ¥38,000	Single room
	Type-B: ¥35,000	Two-person-use of double room
	Type-C: ¥31,000	Three-person-use of triple room

Fees of type-A, -B, -C all cover (1) registration fee (11,000 yen), (2) room charge per one person for the nights of 26th (Monday) and 27th (Tuesday) of October, 2001, (3) six meals from the dinner of the 26th (banquet) through the lunch of 28th, and (4) proceedings of Forum. The rooms of all types A, B, and C have a bath with shower, toilet, and cable TV.

Registration: The registration form can be obtained on request. The request should be made by E-mail, FAX, or postal mail to:

Toshimitsu Tamura
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Technical Development Bureau, Nippon Steel Corporation
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Fax: +81 439 80 2738
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Deadline: October 10, 2001.

Further information: Dr. H. Yamada-Kaneta (Fujitsu Laboratories Ltd.).

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